

High Temperature Gallium Nitride-Based Sensors and Electronics

ATMI, Inc.
Danbury, CT



INNOVATION

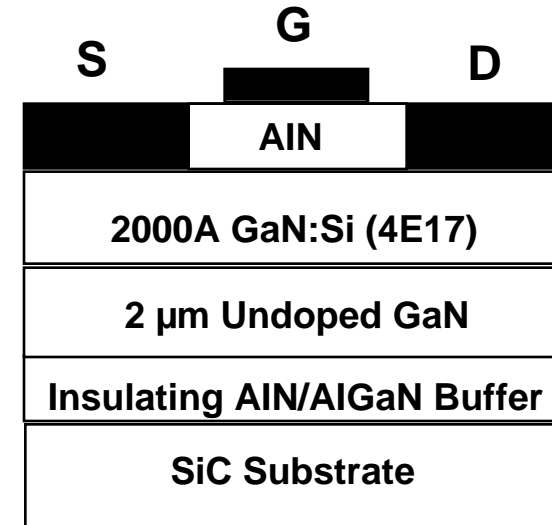
Developed high quality GaN materials that demonstrate great potential for light emitting and electronic devices.

ACCOMPLISHMENTS

- ◆ Developed high quality GaN on SiC.
- ◆ Developed the growth technology of MIS capacitors and MISFETs on GaN using an insulating AlN epitaxial layer.
- ◆ Developed an x-ray simulation program for hexagonal lattice materials.
- ◆ ATMI has developed and patented processes that allow the manufacture of high-purity GaN wafers 50mm and larger in diameter.

COMMERCIALIZATION

- ◆ GaN epitaxial films on SiC have been made commercially available with the support of the SBIR program.
- ◆ Based on recent epitaxy and substrate successes, ATMI has committed significant additional funding for continued GaN wafer development and pilot manufacturing capacity.
- ◆ Jointly developing with an industrial partner a high temperature piezoelectric sensor module to measure gas pressure in high temperature engines.
- ◆ Several jobs created to support this new technology.



**GaN/AlN MISFET Structure
on SiC Substrates**

GOVERNMENT/SCIENCE APPLICATIONS

- ◆ ATMI has recently been awarded contracts totaling nearly \$4M from the Office of Naval Research (ONR) and the Ballistic Missile Defense Operation (BMDO) to further develop GaN wafers for electronic and optoelectronic devices.
- ◆ GaN materials are key to the development of amplifiers operating at > 350 degrees C. The amplifiers are the basis for various applications not currently accessible using Si-based electronics such as in aircraft engine sensors, and ground-vehicle motor control.

Points of Contact:

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